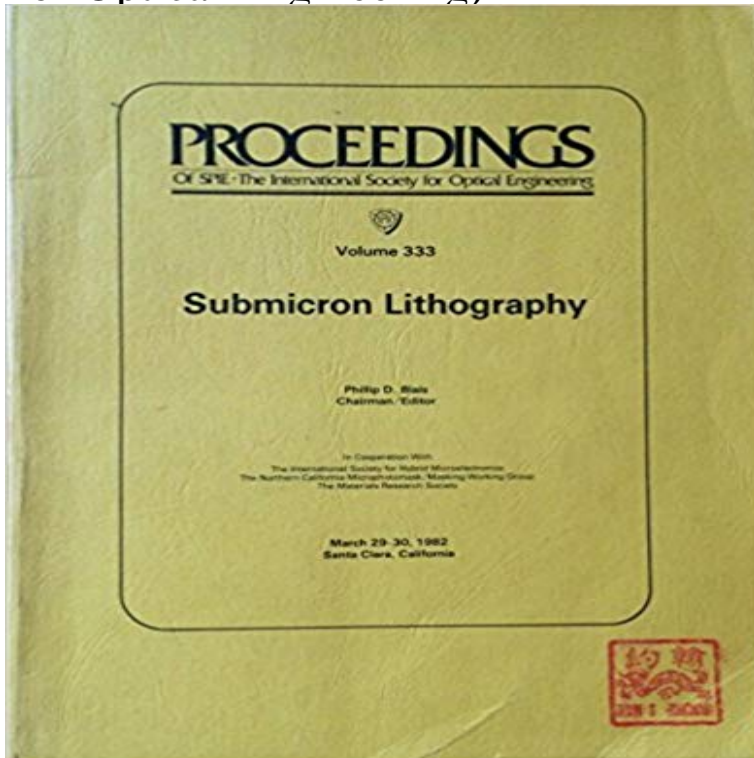


# Submicron lithography (Proceedings of SPIE--the International Society for Optical Engineering)



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